

10/554380

<p align="center"><b>NATIONAL PHASE UTILITY APPLICATION</b></p> <p align="center"><b>Transmittal to the (DO/EO/US) Under 35 USC 371</b></p>	<p>Attorney Docket No.: SHIGA7.032APC          First Named Inventor: Takuma Hojo          Int'l Application No.: PCT/JP2004/005804          Int'l Filing Date: April 22, 2004          Priority Date Claimed: April 30, 2003          Title: POSITIVE PHOTORESIST COMPOSITION AND          METHOD FOR FORMING RESIST PATTERN          Express Mail Label No.: EV211991151US</p>
<p><b>Direct all correspondence to Customer No.: 20995</b> <span style="float: right;">Date: October 26, 2005 Page 1 of 2</span></p>	

**Mail Stop PCT**  
 United States Patent and Trademark Office  
 P.O. Box 1450  
 Alexandria VA 22313-1450

The following enclosures are transmitted herewith to be filed in the patent application of:

**Inventors:**

- |                      |                     |
|----------------------|---------------------|
| 1. Takuma Hojo       | 2. Kiyoshi Ishikawa |
| 3. Tsuyoshi Nakamura | 4. Tasuku Matsumiya |

**APPLICATION ELEMENTS:**

- (X) This is a FIRST submission of items concerning a filing under 35 U.S.C. § 371.
- ~~(X) The U.S. has been elected (Article 31)~~ *PEA 10/26/05*
- (X) A copy of the International Application as filed (35 U.S.C. § 371(c)(2)) has been communicated by the International Bureau.
- (X) PCT/IB/308 enclosed.
- (X) An English translation of the International Application as filed is attached hereto.
- (X) Amendments to the claims of the International Application under PCT Article 19 (35 U.S.C. § 371(c)(3)) have not been and will not be made.

**OTHER APPLICATION PARTS:**

- (X) Preliminary Amendment in 3 pages.
- (X) An Information Disclosure Statement and PTO/SB/08 equivalent listing references for consideration:
- (X) Listing 14 references.
- (X) Enclosing 10 references.
- (X) Cover page of PCT publication WO 2004/097526 A1.
- (X) International Search Report (PCT/ISA/210)
- (X) Written Opinion (PCT/ISA/237)
- (X) Return prepaid postcard.


<b>NATIONAL PHASE UTILITY APPLICATION</b>  <b>Transmittal to the (DO/EO/US) Under 35 USC 371</b>	Attorney Docket No.: SHIGA7.032APC First Named Inventor: Takuma Hojo Int'l Application No.: PCT/JP2004/005804 Int'l Filing Date: April 22, 2004 Priority Date Claimed: April 30, 2003 Title: POSITIVE PHOTORESIST COMPOSITION AND METHOD FOR FORMING RESIST PATTERN Express Mail Label No.: EV211991151US
<div style="display: flex; justify-content: space-between;"> <span><b>Direct all correspondence to Customer No.: 20995</b></span> <span>Date: October 26, 2005 Page 2 of 2</span> </div>	

**FILING FEES:**

FEE CALCULATION				
FEE TYPE & DETERMINATION		LARGE FEE	CALCULATION	TOTAL
Basic Filing Fee under 1.492(a)		1631 (\$300)		\$300
Search Fee under 1.492(b) (enter one in TOTAL column)				
(1) USPTO was ISA and claims are novel		1640 (\$0)		\$400
(2) USPTO was the ISA		1641 (\$100)		
(3) Foreign Search Report Enclosed		1642 (\$400)		
(4) No Search Report Enclosed		1632 (\$500)		
Examination Fee under 1.492(c) (enter one in TOTAL column)				
(1) USPTO was IPEA & claims satisfy Art. 33 (1)-(4))		1643 (\$0)		\$200
(2) Non US IPEA / Noncompliant Claims		1633 (\$200)		
Excess Claims	13 - 20 = 0	1615 (\$50)	0 x 50 =	\$0
Excess Ind. Claims	1 - 3 = 0	1614 (\$200)	0 x 200 =	\$0
Multiple Dep. Claim		1616 (\$360)		\$0
Application Size Fee	0 - 100 = 0	1681 (\$250)	0 x 250 =	\$0
Late English Translation		1618 (\$130)		\$0
Assignment		8021 (\$40)	0 x 40 =	\$0
			<b>TOTAL FEE DUE</b>	<b>\$900</b>
<b>TOTAL FEE PAID (If Different Than Fee Due)</b>				<b>\$</b>

(X) A check in the amount of \$900 to cover the Total Fee Due is enclosed.

The Commissioner is hereby authorized to charge any additional fees which may be required, now or in the future, or credit any overpayment to Account No. 11-1410.

  
 Daniel E. Altman  
 Registration No. 34,115  
 Attorney of Record  
 Customer No. 20,995  
 (949) 760-0404

Daniel E. Altman

MAIL STOP PCT  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450


**CERTIFICATE OF MAILING BY "EXPRESS MAIL"**

**Attorney Docket No.** : SHIGA7.032APC  
**Applicant(s)** : Hojo et al.  
**For** : POSITIVE PHOTORESIST COMPOSITION  
AND METHOD FOR FORMING RESIST  
PATTERN  
**Attorney** : Daniel E. Altman  
**"Express Mail" Label No.** : EV211991151US  
**Date of Deposit** : October 26, 2005

I hereby certify that the accompanying

Transmittal letter; English translation of specification in 32 pages; Preliminary Amendment in 3 pages; cover page of PCT publication; International Search Report and Written Opinion; PCT/IB/308; Information Disclosure Statement, PTO Form PTO/SB/08 Equivalent with 10 references; Check for Filing Fee; Return Prepaid Postcard

are being deposited with the United States Postal Service "Express Mail Post Office to Addressee" service under 37 CFR 1.10 on the date indicated above and are addressed to the Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.

  
Nelson Merida

2019770:vr  
102505